

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>	Docket Number (Optional) <b>TWI-13810</b>	Application Number <b>NEW</b>
	Applicant(s) <b>Martin Ebert</b>	
	Filing Date <b>HEREWITH</b>	Group Art Unit <b>Unknown</b>

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 10/042592  
 01/09/02

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>gl</i>	AA	5,608,526	03/04/1997	Piwonka-Corle et al.	356	369	01/19/1995
<i>gl</i>	AB	5,867,276	02/02/1999	McNeil et al.	356	445	03/07/1997
<i>gl</i>	AC	5,963,329	10/05/1999	Conrad et al.	356	372	10/31/1997
<i>gl</i>	AD	5,973,787	10/26/1999	Aspnes et al.	356	369	05/12/1998
<i>gl</i>	AE	6,031,614	02/29/2000	Michaelis et al.	356	369	12/02/1998
<i>gl</i>	AF	6,278,519	08/21/2001	Rosencwaig et al.	356	369	01/29/1998

**FOREIGN PATENT DOCUMENTS**

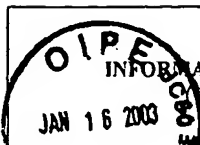
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

**OTHER DOCUMENTS**

*(Including Author, Title, Date, Pertinent Pages, Etc.)*

<i>gl</i>	AG	N. Blayo et al., "Ultraviolet-visible ellipsometry for process control during the etching of submicrometer features," <i>J. Opt. Soc. AM. A</i> , Vol. 12, No. 3, March 1995, pp. 591-599.					
<i>gl</i>	AH	K. Hoshi et al., "KrF Resist Pattern Monitoring by Ellipsometry," <i>Jpn. J. Appl. Phys.</i> , Vol. 36, 1997, pp. 7717-7719.					

Examiner <i>Seigfried Sauer</i>	Date Considered <b>10/26/03</b>
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

	Docket Number (Optional)	Application Number
	TWI-13810	10/042,592
	Applicant(s)	
	Martin Ebert et al.	
Filing Date		Group Art Unit
January 9, 2002		Unknown

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ll	AJ	4,653,924	03/31/1987	Itonaga et al.	356	369	06/10/1985
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							YES	NO
ll	AO	62069151	03/30/1987	EPC (Abstract - Japan)	G01N	21/88		
ll	AP	04127004	04/28/1992	EPC (Abstract - Japan)	G01B	11/06		
ll	AQ	4-127004	04/28/1992	Japan (w/translation)	G01B	11/06	X	
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ll	AV	"Notification of Transmittal of the International Search Report or the Declaration," in PCT/US02/20293, mailed November 29, 2002, 7 pages in length.

Examiner	Date Considered
	11/26/03
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